

CLAIMS

What is claimed is:

1. A substrate treatment apparatus, comprising:
 - a substrate holding unit holding a substrate to be treated;
 - a substrate spinning unit spinning the substrate to be treated held on said substrate holding unit;
 - a treatment solution supply unit supplying a plurality of treatment solutions onto the substrate to be treated; and
 - a treatment solution collection unit having a plurality of collection tanks placed in a manner to surround a periphery of the substrate to be treated held on said substrate holding unit, and provided to separately collect by kind the treatment solutions scattered by said substrate spinning unit from the substrate to be treated,
 - wherein said treatment solution collection unit collects the treatment solution by one of the collection tanks with inlets of the other collection tanks closed.
2. The substrate treatment apparatus according to claim 1, wherein said treatment solution collection unit has a plurality of fences and drives upwards a predetermined fence to thereby form a conduit of said collection tank which collects the treatment solution.
3. The substrate treatment apparatus according to claim 2, wherein a position of the substrate to be

treated held on said substrate holding unit is located above positions of the fences which are not collecting the treatment solution.

4. The substrate treatment apparatus according to claim 2, wherein:

the fences are arranged overlapping one another in order, from the fence closer to the substrate to be treated, in a manner to close the inlets of the collection tanks; and

said treatment solution collection unit performs collection in order, starting from the collection tank at a position farther from the substrate to be treated.

5. The substrate treatment apparatus according to claim 2, wherein the fence has a tip portion formed to be a reflective face that is curved to reflect the treatment solution scattered from the substrate to be treated to lead the treatment solution into the collection tank selected.

6. The substrate treatment apparatus according to claim 1, wherein exhaust units separately exhausting internal gasses are provided for the collection tanks, respectively.

7. The substrate treatment apparatus according to claim 1, wherein drain units draining the treatment solutions are provided for the collection tanks, respectively.

8. The substrate treatment apparatus according to claim 1, further comprising a cleaning unit cleaning

the inside of said collection tanks.

9. A substrate treatment method, comprising the steps of:

supplying a plurality of treatment solutions onto a held substrate to be treated while spinning the substrate; and

when using a treatment solution collection unit having a plurality of collection tanks placed in a manner to surround a periphery of the substrate to be treated and provided to separately collect by kind the treatment solutions scattered from the substrate to be treated, to collect the treatment solution by one of the collection tanks, collecting the treatment solution only by the one of the collection tanks with inlets of the other tanks closed.

10. The substrate treatment method according claim 9, wherein the treatment solution collection unit has a plurality of fences and drives upwards a predetermined fence to thereby form a conduit of the collection tank which collects the treatment solution.

11. The substrate treatment method according claim 10, wherein a position of the held substrate to be treated is located above positions of the fences which are not collecting the treatment solution.

12. The substrate treatment method according claim 10, wherein:

the fences are arranged overlapping one another in order, from the fence closer to the substrate to be treated, in a manner to close the inlets of the

collection tanks; and

 said step of collecting the treatment solution performs collection in order, starting from the collection tank at a position farther from the substrate to be treated.

13. The substrate treatment method according claim 10, wherein the fence has a tip portion formed to be a reflective face that is curved to reflect the treatment solution scattered from the substrate to be treated to lead the treatment solution into the collection tank selected.

14. The substrate treatment method according claim 9, further comprising an exhausting step of separately exhausting internal gasses for the collection tanks, respectively.

15. The substrate treatment method according claim 9, further comprising a drain step of draining the treatment solutions for the collection tanks, respectively.

16. The substrate treatment method according claim 9, further comprising a cleaning step of cleaning the inside of the collection tanks.